

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Tsuyoshi NAKAMURA, et al.

Application No.: To be assigned

Group Art Unit: To be assigned

Confirmation No.: To be assigned

Examiner: To be assigned

Filed: July 11, 2001

For: NOVEL COPOLYMER, PHOTORESIST COMPOSITION, AND PROCESS FOR  
FORMING RESIST PATTERN WITH HIGH ASPECT RATIO

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231

Sir:

**IN THE CLAIMS:**

**Please enter the following amended claims:**

9. (Amended) A novel copolymer according to claim 1, wherein said novel copolymer has a weight average molecular weight (Mw) in terms of polystyrene of from 7000 to 30000 and a molecular-weight distribution (Mw/Mn, where Mn is a number average molecular weight) of equal to or less than 3.5.

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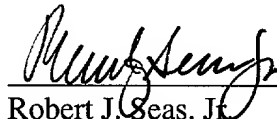
**PRELIMINARY AMENDMENT**  
**U.S. Application No. To be assigned**

**Attorney Docket No. Q65210**

**REMARKS**

The foregoing amendments are made in order to remove multiple dependencies and avoid the Government surcharge. Entry and consideration of this Amendment is respectfully requested.

Respectfully submitted,

  
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Date: July 11, 2001

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**APPENDIX**  
**VERSION WITH MARKINGS TO SHOW CHANGES MADE**

**IN THE CLAIMS:**

**The claims are amended as follows:**

9. (Amended) A novel copolymer according to ~~any one of claims 1 to 8~~ claim 1, wherein said novel copolymer has a weight average molecular weight ( $M_w$ ) in terms of polystyrene of from 7000 to 30000 and a molecular-weight distribution ( $M_w/M_n$ , where  $M_n$  is a number average molecular weight) of equal to or less than 3.5.

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